

Claim 20, line 2, change "19" to --16--.

Claim 21, change "20" to --16--.

Claim 23, delete "or 22".

Claim 24, delete "any of the claims 21 to 23" and insert --claim 21--.

Claim 25, change "24" to --16--.

Claim 26, change "25" to --16--.

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27. (Amended) An electron beam drawing mask, manufactured by using the mask blank as claimed any of the claims 1 to [26] 5 and 13 to 16.

Claim 36, line 2, change "27" to --28--.

Claim 37, line 4, change "36" to --35--.

Claim 39, line 2, change "36" to --35--.

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--40. An electron beam drawing mask blank as claimed in claim 2, further comprising an etching stopper layer sandwiched either between said electron beam scattering layer and said pattern supporting layer or between said pattern supporting layer and said support member.

41. An electron beam drawing mask blank as claimed in claim 3, further comprising an etching stopper layer sandwiched either between said electron beam scattering layer and said pattern supporting layer or between said pattern supporting layer and said support member.

42. An electron beam drawing mask blank as claimed in claim 4, further comprising an etching stopper layer sandwiched either between said electron beam scattering layer and said pattern supporting layer or between said pattern supporting layer and said support member.

43. An electron beam drawing mask blank as claimed in claim 5, further comprising an etching stopper layer sandwiched either between said electron beam scattering layer and said pattern supporting layer or between said pattern supporting layer and said support member.

44. An electron beam drawing mask blank as claimed in claim 6, further comprising an etching stopper layer sandwiched either between said electron beam scattering layer and said pattern supporting layer or between said pattern supporting layer and said support member.

45. An electron beam drawing mask blank as claimed in claim 7, further comprising an

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cont.

etching stopper layer sandwiched either between said electron beam scattering layer and said pattern supporting layer or between said pattern supporting layer and said support member.

46. An electron beam drawing mask blank as claimed in claim 8, further comprising an etching stopper layer sandwiched either between said electron beam scattering layer and said pattern supporting layer or between said pattern supporting layer and said support member.

47. An electron beam drawing mask blank as claimed in claim 9 further comprising an etching stopper layer sandwiched either between said electron beam scattering layer and said pattern supporting layer or between said pattern supporting layer and said support member.

48. An electron beam drawing mask blank as claimed in claim 40, wherein said etching stopper layer is made of a material having a high etching selection ratio with said electron beam scattering layer and/or said support member.

49. An electron beam drawing mask blank as claimed in claim 41, wherein said etching stopper layer is made of a material having a high etching selection ratio with said electron beam scattering layer and/or said support member.

50. An electron beam drawing mask blank as claimed in claim 42, wherein said etching stopper layer is made of a material having a high etching selection ratio with said electron beam scattering layer and/or said support member.

51. An electron beam drawing mask blank as claimed in claim 43, wherein said etching stopper layer is made of a material having a high etching selection ratio with said electron beam scattering layer and/or said support member.

52. An electron beam drawing mask blank as claimed in claim 44, wherein said etching stopper layer is made of a material having a high etching selection ratio with said electron beam scattering layer and/or said support member.

53. An electron beam drawing mask blank as claimed in claim 45, wherein said etching stopper layer is made of a material having a high etching selection ratio with said electron beam scattering layer and/or said support member.

54. An electron beam drawing mask blank as claimed in claim 46, wherein said etching stopper layer is made of a material having a high etching selection ratio with said electron beam scattering layer and/or said support member.

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cont.

55. An electron beam drawing mask blank as claimed in claim 47, wherein said etching stopper layer is made of a material having a high etching selection ratio with said electron beam scattering layer and/or said support member.

56. An electron beam drawing mask blank as claimed in claim 2, wherein said support member is made of a material composed substantially of the carbon element.

57. An electron beam drawing mask blank as claimed in claim 3 wherein said support member is made of a material composed substantially of the carbon element.

58. An electron beam drawing mask blank as claimed in claim 4 wherein said support member is made of a material composed substantially of the carbon element.

59. An electron beam drawing mask blank as claimed in claim 5, wherein said support member is made of a material composed substantially of the carbon element.

60. An electron beam drawing mask blank as claimed in claim 6, wherein said support member is made of a material composed substantially of the carbon element.

61. An electron beam drawing mask blank as claimed in claim 7, wherein said support member is made of a material composed substantially of the carbon element.

62. An electron beam drawing mask blank as claimed in claim 8, wherein said support member is made of a material composed substantially of the carbon element.

63. An electron beam drawing mask blank as claimed in claim 9, wherein said support member is made of a material composed substantially of the carbon element.

64. An electron beam drawing mask blank as claimed in claim 10, wherein said support member is made of a material composed substantially of the carbon element.

65. An electron beam drawing mask blank as claimed in claim 40, wherein said support member is made of a material composed substantially of the carbon element.

66. An electron beam drawing mask blank as claimed in claim 41, wherein said support member is made of a material composed substantially of the carbon element.

67. An electron beam drawing mask blank as claimed in claim 42, wherein said support member is made of a material composed substantially of the carbon element.

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cont.

68. An electron beam drawing mask blank as claimed in claim 43, wherein said support member is made of a material composed substantially of the carbon element.

69. An electron beam drawing mask blank as claimed in claim 44, wherein said support member is made of a material composed substantially of the carbon element.

70. An electron beam drawing mask blank as claimed in claim 45, wherein said support member is made of a material composed substantially of the carbon element.

71. An electron beam drawing mask blank as claimed in claim 46, wherein said support member is made of a material composed substantially of the carbon element.

72. An electron beam drawing mask blank as claimed in claim 48, wherein said support member is made of a material composed substantially of the carbon element.

73. An electron beam drawing mask blank as claimed in claim 49, wherein said support member is made of a material composed substantially of the carbon element.

74. An electron beam drawing mask blank as claimed in claim 50, wherein said support member is made of a material composed substantially of the carbon element.

75. An electron beam drawing mask blank as claimed in claim 51, wherein said support member is made of a material composed substantially of the carbon element.

76. An electron beam drawing mask blank as claimed in claim 52 wherein said support member is made of a material composed substantially of the carbon element.

77. An electron beam drawing mask blank as claimed in claim 53, wherein said support member is made of a material composed substantially of the carbon element.

78. An electron beam drawing mask blank as claimed in claim 54, wherein said support member is made of a material composed substantially of the carbon element.

79. An electron beam drawing mask blank as claimed in claim 55, wherein said support member is made of a material composed substantially of the carbon element.

80. An electron beam drawing mask blank as claimed in claim 56, wherein said support member is made of a material composed substantially of the carbon element.

81. An electron beam drawing mask blank as claimed in claim 17, wherein said pattern supporting layer and/or said electron beam scattering layer have elastic moduli of 0.8 x

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conc.

10<sup>11</sup> Pa or higher.

82. An electron beam drawing mask blank as claimed in claim 17, wherein said pattern supporting layer and/or said electron beam scattering layer have a film thickness dispersion of 30 % or less within one shot area.

83. An electron beam drawing mask blank as claimed in claim 17, wherein said electron beam scattering layer is made of a material composed substantially of the carbon element and/or the silicon element.

84. An electron beam drawing mask blank as claimed in claim 18, wherein said electron beam scattering layer is made of a material composed substantially of the carbon element and/or the silicon element.

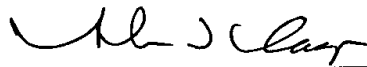
85. An electron beam drawing mask blank as claimed in claim 18, wherein said electron beam scattering layer is made of a material composed substantially of the carbon element and/or the silicon element.

86. An electron beam drawing mask blank as claimed in claim 19, wherein said electron beam scattering layer is made of a material composed substantially of the carbon element and/or the silicon element.--

#### REMARKS

Entry and consideration of this Amendment is respectfully requested.

Respectfully submitted,



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